

REMARKS

Applicants thank Examiner Vinh for the careful examination of this application and for the allowance of the claims.

Applicants amend the specification in page 7 according to of Examiner Vinh's suggestion.

Applicants amend claim 15 to specify that the 5% voltage change is in reference to a specific reference voltage to point out particularly the claimed invention. This specific reference voltage is the relatively constant voltage measured at the element during the etching of the targeted material. This is clear by reading the specification and viewing the drawing figures. In the case of the embodiment shown in Figure 3, the reference voltage is about 105 volts; in case of the embodiment shown in Figure 4, the reference is about 90 volts; and in the case of the embodiment shown in Figure 5, it is about 110 volts.

Applicants further cancel claims 8-10 and 16-18 to put this application in the form for allowance.

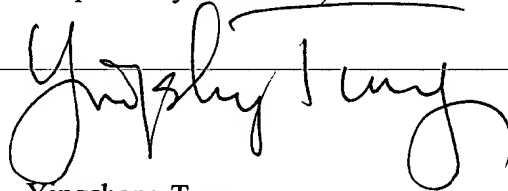
Applicants amend the drawing figure 3, 4, and 5 without adding any new matter to make them more consistent and to make them more helpful in understanding the invention. In figures 3, 4, and 5, the curves for the end-point display (EPD) method are thickened and with a pointer added pointing to the right to indicate that the scale for the each EPD curve is to the right (in percentage), and the scale to the left (in volts) is for the signal of this new end-point control process and system. This is to distinguish the two curves more clearly in figures 3, 4, and 5.

Examiner Vinh is correct in defining the claim language of "within a predetermined time" as being 80 seconds in the example on page 9 of the specification. As is well known in the art of plasma etching, the total etch time is a function of the etch rate of the reaction and the thickness of the layer of the targeted material. The etch rate is in turn a function of the plasma reactor, the etch chemistry, the composition of the targeted material, and the power of the plasma, among other factors. Therefore, the

predetermined time will change depending on at least the factors above and still be within the scope of the present invention.

Applicants respectfully submit that the application is in allowable form and the claims distinguish over the cited references. Applicants respectfully request the reconsideration or further examination of this application.

Respectfully submitted,

A handwritten signature in cursive script, appearing to read 'Yingsheng Tung', written in black ink.

Yingsheng Tung
Reg. No. 52,305
Attorney for Applicants

Texas Instruments Incorporated
P. O. Box 655474, MS 3999
Dallas, Texas 75265
(972) 917-5355